

# Optical Standards for Integrated Circuit Dimensional Metrology

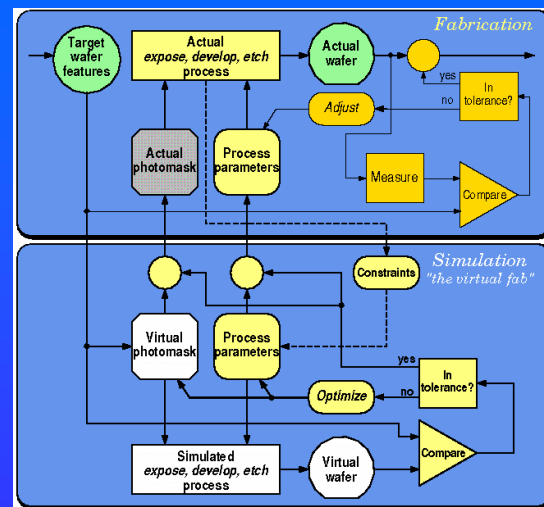
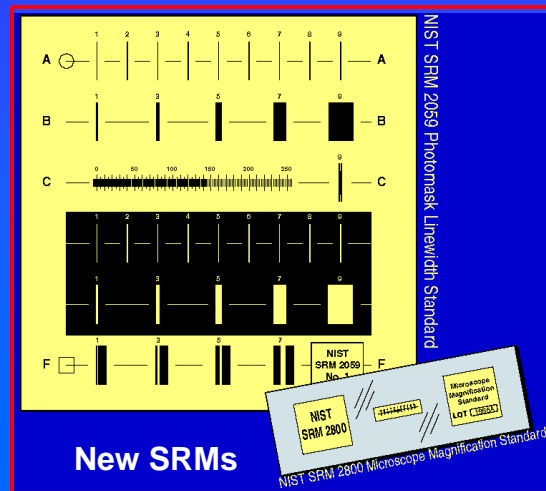
## Project Leader: James Potzick

### 2001 Deliverables

- Complete the calibrations and documentation necessary for the issuance of Standard Reference Material SRM 2800 (a new NIST traceable scale micrometer).
- Complete the calibrations and documentation necessary for the issuance of Standard Reference Material SRM 2059 the new photomask linewidth standard

### Customers and Collaborators

- International SEMATECH
- Office of Microelectronics Programs
- The Neolithography Group
- BIPM



Process modeling  
for improved metrology

### FY 2000 Accomplishments

- The NIST UV Scanning Microscope modified, improved, and in production, calibrating SRM 2800.
- Library of modeled photomask line images being developed.
- SEMI Standards task force document Terminology for Microlithography Metrology has become SEMI Standard P35.
- Invited paper Photomask metrology and neolithography presented at Advanced Reticle Symposium in San Jose, Calif.
- Neolithography Group coordination transferred to International SEMATECH